



Attorney's Docket No.: 042390P10625

RESPONSE UNDER 37 C.F.R. § 1.116
EXPEDITED PROCEDURE
EXAMINING GROUP 2825

Patent

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:

Jack Hwang, et al.

Application No.: 09/887,910

Filed: June 22, 2001

For: A METHOD OF MAKING A
SEMICONDUCTOR TRANSISTOR
BY IMPLANTING IONS INTO A
GATE DIELECTRIC LAYER THEREOF

Examiner: Igwe U. Anya

Art Unit: 2825

Mail Stop AF
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

RESPONSE AFTER FINAL ACTION UNDER 37 C.F.R. § 1.116

Dear Sir:

In response to the Final Office Action mailed on August 20, 2003, Applicant respectfully requests that the Examiner reconsider the application in light of the following remarks.

FIRST CLASS CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as first-class mail with sufficient postage in an envelope addressed to the Assistant Commissioner for Patents, Washington, D.C., 20231 on:

October 17, 2003

Date of Deposit

Linda K. Brost

Name of Person Mailing Correspondence

Linda K. Brost

Signature

October 17, 2003

Date

Jack Hwang, et al.
Serial No.: 09/887,910

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